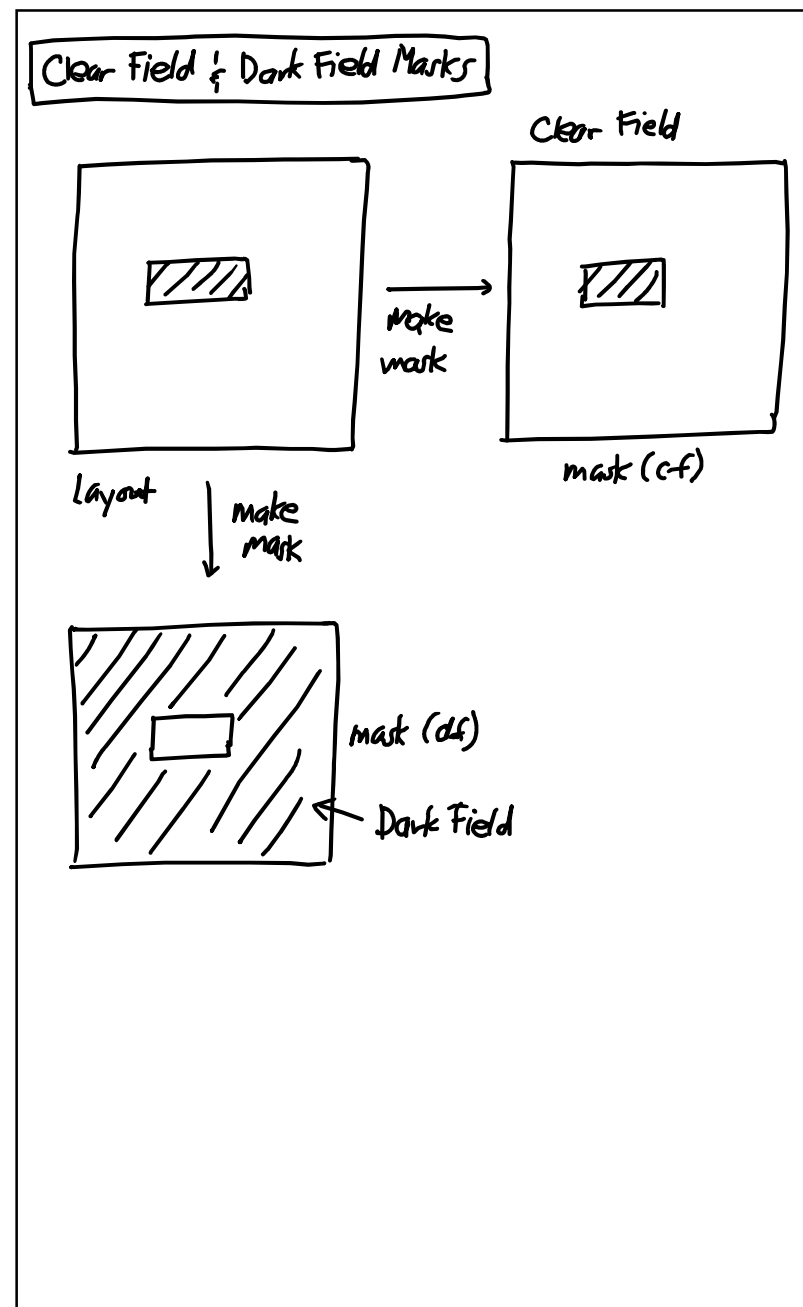


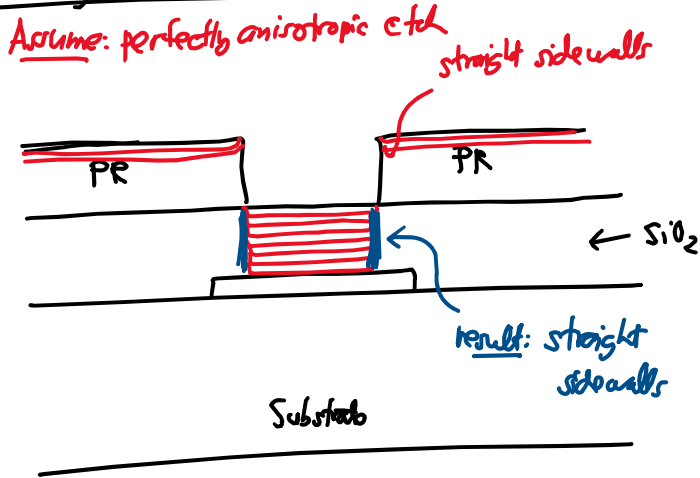
Lecture 7: Surface Micromachining I

- Announcements:
- HW#2 due Thursday, 2/21 at 9 a.m.
- Surface Micromachining Module 5 & Handouts online
- -----
- Today:
- Senturia, Chpt. 3; Jaeger, Chpt. 2, 3, 6
- Lecture Topics:
  - ↳ Example MEMS fabrication processes
  - ↳ Photolithography
  - ↳ Etching
  - ↳ Oxidation
  - ↳ Film Deposition
  - ↳ Diffusion
  - ↳ Ion Implantation
- Reading: Senturia Chpt. 3, Jaeger Chpt. 11, Handouts: "Surface Micromachining for Microelectromechanical Systems", "Etch Rates for Micromachining—Part II"
- Lecture Topics:
  - ↳ Polysilicon surface micromachining
  - ↳ Stiction
  - ↳ Residual stress
  - ↳ Topography issues
  - ↳ Nickel metal surface micromachining
  - ↳ 3D "pop-up" MEMS
  - ↳ Foundry MEMS: the "MUMPS" process
  - ↳ The Sandia SUMMIT process
- -----
- Last Time: Diffusion section of Module 4

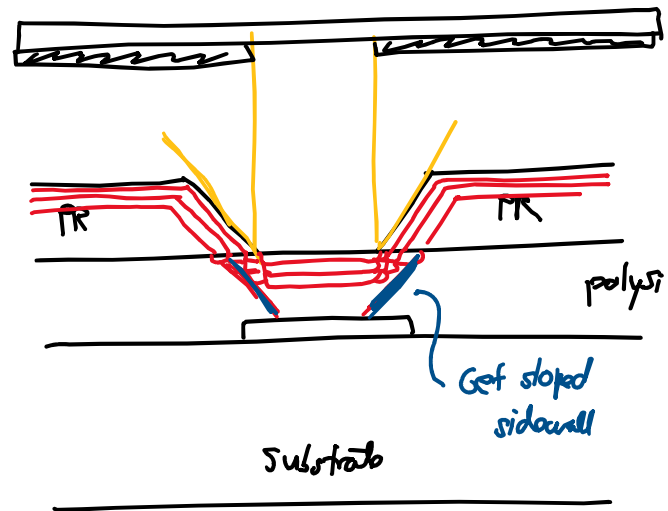


- Straight or Sloped Sidewalls:
- Often want sloped sidewalls in order to reduce the sharpness of corners
  - ↳ Easier to deposit over
  - ↳ Sharp corners concentrate stresses
  - ↳ High stress can weaken structures creating a reliability concern
  - ↳ High stress can dissipate energy, lowering Q
- When you want straight sidewalls (e.g., for lateral electrostatic drive), use a hard mask
  - ↳ PR can't last for thick structures
  - ↳ A hard mask suppresses angle transfer

Etching Sloped or Straight Sidewalls



Reality: PR will be sloped *Anisotropic Etch (still)*



Remarks:

- ① If want sloped sidewalls → over-expose the PR
- But if want straight sidewalls:

